

3 2  
19. The polishing pad of claim 18, wherein the transparent section extends through the first layer.

4 2  
20. The polishing pad of claim 18, wherein the aperture extends through the second layer.

5 1  
21. The polishing pad of claim 17, wherein the transparent section and the aperture have substantially the same dimension.

6 1  
22. The polishing pad of claim 17, wherein a top surface of the transparent section is substantially coplanar with the polishing surface.

7 23. A polishing pad for a chemical mechanical polishing apparatus, comprising:  
a first layer having a polishing surface and a transparent section; and  
a second layer adjacent to the first layer having an aperture substantially aligned with the transparent section. *Layer 18 and 20 of 7 can be underneath each other*

8 24. The polishing pad of claim 23, wherein the first layer is formed of a polyurethane material.

9 25. The polishing pad of claim 25, wherein the transparent section is formed of a polyurethane material.

10 26. The polishing pad of claim 23, wherein the second layer is a backing layer.

11 27. A polishing pad for a chemical mechanical polishing apparatus, comprising:

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~~Sub 3~~  
~~D 23~~  
~~A 25~~  
an article having a polishing surface and a substantially transparent section, the transparent section having a first portion with a first dimension and a second portion with a second, different dimension.

~~12~~ 11  
28. The polishing pad of claim ~~27~~, wherein the article includes a first layer with the polishing surface and a second layer adjacent to the first layer.

~~13~~ 12  
29. The polishing pad of claim ~~28~~, wherein the transparent section extends through the first and second layers.

~~14~~ 13  
30. The polishing pad of claim ~~29~~, wherein the first section of the aperture extends through the first layer and the second section of the aperture extends through the second layer.

~~15~~ 13  
31. A chemical mechanical polishing apparatus, comprising:  
a carrier head to hold a substrate;  
a polishing pad having a polishing surface and a surface opposite the polishing surface, the polishing pad including a first layer having a polishing surface with a transparent section and a second layer adjacent to the first layer having an aperture substantially aligned with the transparent section; and

a motor to generate relative motion between the carrier head and the polishing pad.

~~16~~ 15  
32. The apparatus of claim ~~31~~, further comprising a platen to support the polishing pad.

~~17~~ 16  
33. The apparatus of claim ~~32~~, wherein the second layer abuts the platen.

~~18~~ 17  
34. The apparatus of claim ~~33~~, wherein a passage is formed in the platen, and the passage is substantially aligned with the aperture in the polishing pad.

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